

Electronic Patent Application Fee Transmittal

Application Number:	10587194			
Filing Date:	24-Jul-2006			
Title of Invention:	PROTECTED PATTERN MASK FOR REFLECTION LITHOGRAPHY IN THE EXTREME UV OR SOFT X-RAY RANGE			
First Named Inventor/Applicant Name:	Jean-Louis Stehle			
Filer:	Mark E. Garscia/Christine Sherwood			
Attorney Docket Number:	58059/N75			
Filed as Large Entity				
U.S. National Stage under 35 USC 371 Filing Fees				
Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Basic Filing:				
Pages:				
Claims:				
Miscellaneous-Filing:				
Petition:				
Patent-Appeals-and-Interference:				
Post-Allowance-and-Post-Issuance:				
Utility Appl issue fee	1501	1	1510	1510
Publ. Fee- early, voluntary, or normal	1504	1	300	300

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Extension-of-Time:				
Miscellaneous:				
Printed copy of patent - no color	8001	3	3	9
Total in USD (\$)				1819